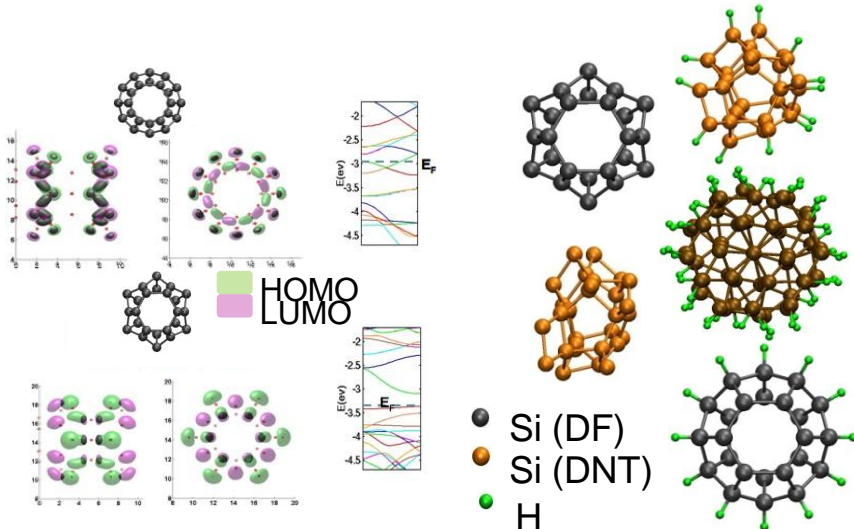


Surface and strain effects in nanostructures and nanodevices

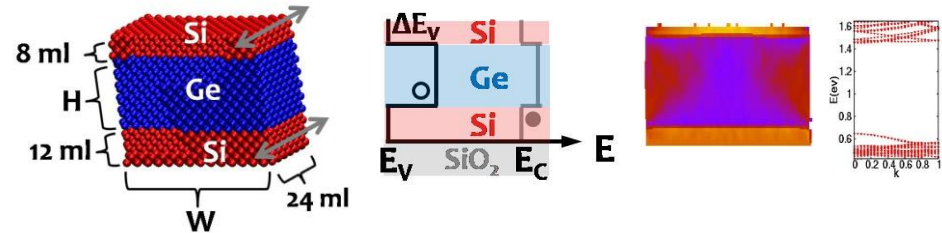
Methods employed/ developed: DFT, reactive FF MD, modified tight binding

~1nm dia silicon nanowires

- Goal: exploration of new materials, photovoltaics, sensors, thermoelectrics, CMOS scaling, batteries
- energetically most stable wires (2 categories)
- tubelike: non-bulk geometries
- new bandgap ranges, unique properties
- surfaces => structural symmetry => properties

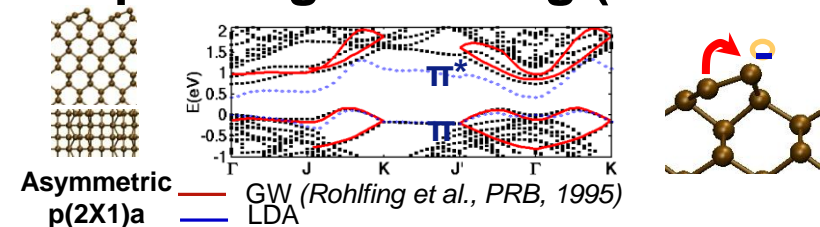


Electrical properties of Si-Ge-Si bars



- Goal: High performance electronics
- inhomogeneous strain in Ge: reduced hole effective mass
- bandgap between uniaxial and biaxial

Adaptive tight binding (Si surface)



- Goal: nanoelectronics (modified bonding), defects/ scattering in large systems
- modified TB parameters => good match with GW